

SHEET FOR MASK

ABSTRACT

Object is to provide a sheet for mask excellent in pollen adhesion preventing performance.

The present invention provides a sheet for mask having a base material coated with a coating agent containing a silicon-based compound and a cationic antistatic agent; and a mask using the sheet for mask. The present invention makes it possible to provide a sheet for mask and a mask excellent in pollen adhesion preventing performance.

Figure 1 (a) and (b)